ULSI Process Integration 8

Editors:

C. Claeys
IMEC
Leuven, Belgium

M. Tao
University of Texas at Arlington
Arlington, Texas, USA

J. Murota
Tohoku University
Sendai, Japan

H. Iwai
Tokyo Institute of Technology
Tokyo, Japan

S. Deleonibus
CEA-LETI
Grenoble, France

Sponsoring Division:

Electronics and Photonics

Published by
The Electrochemical Society
65 South Main Street, Building D
Pennington, NJ 08534-2839, USA
tel 609 737 1902
fax 609 737 2743
www.electrochem.org

ecs transactions ™

Vol. 58, No. 9

Published by:

The Electrochemical Society
65 South Main Street
Pennington, New Jersey 08534-2839, USA

Telephone 609.737.1902
Fax 609.737.2743
e-mail: ecs@electrochem.org
Web: www.electrochem.org

ISSN 1938-6737 (online)
ISSN 1938-5862 (print)
ISSN 2151-2051 (cd-rom)

ISBN 978-1-62332-100-0 (Hardcover)
ISBN 978-1-60768-454-1 (PDF)

Printed in the United States of America.

***ECS Transactions*, Volume 58, Issue 9**
ULSI Process Integration 8

Table of Contents

Chapter 3
Single Electron, Tunneling and Quantum Devices

Chapter 4
Technology Trends

Chapter 5
Ge-based and III-V Technologies

Chapter 6
Epitaxial Processing

Chapter 8
Device Characterization